

ABSTRACT

An object of the present invention is to provide a photoresist stripping composition which exhibits high stripping performance even for a cured resist, prevents corrosion of substrate-forming metals, such as Cu and Al, that come in contact with a liquid, and can prevent excessive oxidation of a metal such as Cu during a stripping process. The object was achieved by a photoresist stripping composition, the composition containing a quaternary ammonium hydroxide (A), diethylene glycol monoethyl ether (B), glycerin (C), and water (D), wherein a content of (A) is 0.5 to 5 mass% with respect to a total mass of the composition, a content of (B) is 50 to 95 mass% with respect to the total mass of the composition, a content of (C) is 0.5 to 20 mass% with respect to the total mass of the composition, and a content of (D) is less than 20 mass% with respect to the total mass of the composition.

No Figure.